## **Supporting Information**

## Hierarchical TiN Nanoparticles Assembled Nanopillars for Flexible Supercapacitors with High Volumetric Capacitance

Ping Qin,<sup>a+</sup> Xingxing Li,<sup>a+</sup> Biao Gao,<sup>a\*</sup> Jijiang Fu,<sup>a</sup> Lu Xia,<sup>a</sup> Xuming Zhang,<sup>a\*</sup> Kaifu Huo,<sup>b</sup> Wenli Shen<sup>c</sup> and Paul K. Chu<sup>d</sup>

<sup>a</sup> The State Key Laboratory of Refractories and Metallurgy, Institute of Advanced Materials and Nanotechnology, Wuhan University of Science and Technology, Wuhan 430081, China.

<sup>b</sup> Wuhan National Laboratory for Optoelectronics (WNLO), School of Optical and Electronic Information Huazhong University of Science and Technology Wuhan 430074, China.

<sup>c</sup> Department of Physics, Arizona state University, Tempe 85281, USA.

<sup>d</sup> Department of Physics and Department of Materials Science and Engineering, City University of Hong Kong, Tat Chee Avenue, Kowloon, Hong Kong, China.

\* Corresponding author:

E-mail: gaobiao@wust.edu.cn (B. Gao); xumzhang@wust.edu.cn (X. Zhang)



Fig. S1. (a) Top-view and (b) side-view SEM images of the  $TiO_2$  NTs; (c) Top-view and (d) side-view SEM images of the H-TiO<sub>2</sub> NPs.



Fig. S2. XPS spectra of N 1s of the H-TiN NPs.



Fig. S3. (a)  $N_2$  adsorption-desorption isotherms and (b) the pore size distribution of the H-TiN NPs and TiN NTs.



Fig. S4. CV curves of (a) H-TiN NPs and (b) TiN NTs at different scanning rates from 10 to 200 mV s<sup>-1</sup>.



Fig. S5. GCD curves of the (a) H-TiN NPs and (b) TiN NTs at different current densities from 0.83 to 83 A cm<sup>-3</sup> in 1 M  $H_2SO_4$ .



**Fig. S6.** (a) The electrochemical impedance spectroscopy and (b) the characteristic frequency for a phase angle marks at -45° point of the H-TiN NPs.



Fig. S7. The electrochemical impedance spectroscopy of the TiN NTs.



Fig. S8. The areal specific capacitances of H-TiN NPs at different current densities.



Fig. S9. GCD curves of (a) H-TiN NPs and (b) TiN NTs at a current density of 0.83 A cm<sup>-3</sup> in 0.1 M H<sub>2</sub>SO<sub>4</sub>, 0.1 M HBF<sub>4</sub>, 0.1 M  $[(C_2H_5)_4N]_2SO_4$  and 0.1 M  $[(C_2H_5)_4N]BF_4$ .



**Fig. S10.** The relationship of scan rate and current density of H-TiN NPs and TiN NTs collecting from CV curves at a potential of 0.4 V. The slope value represents the effective active surface area.



**Fig. S11.** Cycling stability of the H-TiN NPs electrode measured by CV at a scanning rate of 200 mV s<sup>-1</sup>.